

AZ 15nXT (450 CPS) – run sheet

AZ Electronic Materials

nanyte.com/photoresists/az-15nxt · last updated 2026-07-26

Thickness: 6.4–14.6 μm

Softbake: 110 °C · 3 min

Exposure dose: 400 mJ/cm² @ 365 nm

Post-exposure bake: 120 °C · 60 s

Develop: Developer AZ 300 MIF · Dilution 2.38% TMAH (AZ 300 MIF, ready-to-use) · Method puddle